L Number	7724	Search Text	I DD	I m t m a set
	1715	<u> </u>	DB USPAT;	Time stamp 2004/05/04 11:22
-37	1/13	((118//19) or (414/939) or (136/345.31) or (156/345.32)).CCLS.	US-PGPUB	2004/05/04 11:22
-	11	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 16:14
	**	or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	2003/03/30 16:14
		with chamber with remov\$3 with oxide)	OS IGIOD	
_	152	transfer\$4 with chamber with remov\$3 with	USPAT;	2003/05/29 20:25
	202	oxide	US-PGPUB	2000/00/25 20.25
_	0		USPAT;	2003/05/29 20:29
		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	2000,00,25 20.25
		with chamber with "hf")		
	260	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/29 20:33
		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	
		with chamber with (gas vapor))		
-	29	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/29 20:41
		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	
		with chamber with (gas vapor) with		
}		remov\$3)		
-	2	"11134684"	JPO;	2003/05/29 20:49
			DERWENT	
-	163	sugiura.in. and tokyo.as.	JPO;	2003/05/29 20:49
	_		DERWENT	
-	. 6	sugiura.in. and tokyo.as. and "uv"	JPO;	2003/05/29 20:49
	ا م	/#500000cH	DERWENT	
-	6	("5228206"   "5972161"   "6143081"	USPAT	2003/05/29 20:53
.	_	"6178660"   "6204120"   "6232248").PN.		
_	2	6178660.URPN.	USPAT	2003/05/29 21:00
-	0 13	6467491.URPN.	USPAT	2003/05/29 21:00
-	13	("4795299"   "4917556"   "5228206"	USPAT	2003/05/29 21:01
		"5423971"   "5529657"   "5611861"		
		"5755938"   "5759334"   "5855675"   "5863170"   "5880924"   "5882165"		
		"5863170"   "5880924"   "5882165"   "5886864").PN.		
_	112	imahashi.in.	HCDAM.	2002/05/20 10 14
j 1	112	Imanashi, III.	USPAT; US-PGPUB	2003/05/30 10:14
l <b>-</b>	2	imahashi.in. and 118/719.ccls.	USPAT;	2003/05/30 10:15
] ,	~	Indiabiliting and 1107719.0013.	US-PGPUB	2003/03/30 10:15
Í – I	50	5695564.URPN.	USPAT	2003/05/30 10:31
-	1715	((118/719) or (414/939) or (156/345.31) or	USPAT;	2003/05/30 10:31
	_,	(156/345.32)).CCLS.	US-PGPUB	2003/03/30 10.38
-	94	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 10:41
		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	2003/03/30 10.41
.		with chamber with (inlet ((vapor gas) with	00 10105	
		suppl\$3)))		
-	. 54	c23c016\$.ipc. and (transfer\$4 with chamber	EPO; JPO;	2003/05/30 11:21
	i	<pre>with (inlet suppl\$3) with (vapor gas))</pre>	DERWENT	
	71	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 10:51
	ļ	or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	
	ĺ	with chamber with (inlet suppl\$3) with	_	
		(vapor gas))		
-	0	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 10:54
		or (156/345.32)).CCLS.) and ((transfer\$4	US-PGPUB	
		with chamber with (inlet suppl\$3) with		
	_	(vapor gas)) same align\$4)		
-	0	c23c016\$.ipc. and ((transfer\$4 with	EPO; JPO;	2003/05/30 10:54
		chamber with (inlet suppl\$3) with (vapor	DERWENT	
		gas)) same align\$4)		
-	1	c23c016\$.ipc. and ((transfer\$4 with	EPO; JPO;	2003/05/30 10:55
		chamber with (inlet suppl\$3) with (vapor	DERWENT	
_		gas)) and align\$4)	W055-	
	33	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 11:12
1		or (156/345.32)).CCLS.) and ((transfer\$4	US-PGPUB	
		<pre>with chamber with (inlet suppl\$3) with (vapor gas)) and align\$4)</pre>		
_	. 0	(((118/719) or (414/939) or (156/345.31)	IICDAM -	2002/05/20 11 00
ĺ	- 1	or (156/345.32)).CCLS.) and (transfer\$4	USPAT;	2003/05/30 11:20
		with chamber with (teflon ((silicon with	US-PGPUB	
ļ		carbide) "sic") polytetrafluoroethylene		
	}	(resin\$3 with polymer\$3)))		
_	<sub>0</sub>		USPAT;	2003/05/30 11:21
1		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	2003/03/30 11:21
		with chamber with (teflon ))	US FGFUD	
		"TO" OTTOWNOT MICH (COLITOH )		

					•
		0	or (156/345.32)).CCLS.) and (transfer\$4 with chamber with ((silicon with carbide)	USPAT; US-PGPUB	2003/05/30 11:22
	_	0	"sic" )) (((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$4 with chamber with polytetrafluoroethylene	USPAT; US-PGPUB	2003/05/30 11:21
	-	0	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$4 with chamber with resin\$3 with polymer\$3)	USPAT; US-PGPUB	2003/05/30 11:22
	_	48150		EPO; JPO;	2003/05/30 16:32
	_	0	c23c016\$.ipc. and (transfer\$4 with chamber with (teflon ))	DERWENT EPO; JPO; DERWENT	2003/05/30 11:22
	_	. 0	c23c016\$.ipc. and (transfer\$4 with chamber with polytetrafluoroethylene)	EPO; JPO; DERWENT	2003/05/30 11:24
	- 0	0	c23c016\$.ipc. and (transfer\$4 with chamber with ((silicon with carbide) "sic"	EPO; JPO; DERWENT	2003/05/30 11:25
	_	0	1 ' '	EPO; JPO; DERWENT	2003/05/30 11:24
	_	10	c23c016\$.ipc. and (chamber with (teflon ))	EPO; JPO; DERWENT	2003/05/30 11:22
	-	0	c23c016\$.ipc. and (chamber with resin\$3 with polymer\$3)	EPO; JPO; DERWENT	2003/05/30 11:24
	<b>-</b> .	6	c23c016\$.ipc. and (chamber with polytetrafluoroethylene)	EPO; JPO; DERWENT	2003/05/30 11:24
	_	116		EPO; JPO; DERWENT	2003/05/30 11:25
	-	4	c23c016\$.ipc. and (chamber with ((silicon with carbide) "sic") with corros\$3)	EPO; JPO; DERWENT	2003/05/30 11:25
	_	0	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$4	USPAT; US-PGPUB	2003/05/30 16:30
	_	1	or (156/345.32)).CCLS.) and (transfer\$4	USPAT; US-PGPUB	2003/05/30 16:14
	_	0	or (156/345.32)).CCLS.) and (transfer\$4	USPAT; US-PGPUB	2003/05/30 16:15
	_	1	or (156/345.32)).CCLS.) and (transfer\$4	USPAT; US-PGPUB	2003/05/30 16:15
.	-	1715	with chamber with "hydrofluoric") ((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.	USPAT; US-PGPUB	2003/05/30 18:05
-	_	670	transfer\$4 with chamber with clean\$3 with (wafer substrate semiconductor)	USPAT; US-PGPUB	2003/05/30 16:36
-	-	48150	c23c016\$.ipc.	EPO; JPO; DERWENT	2003/05/30 16:32
-	-	. 158	transfer\$4 with chamber with clean\$3 with (wafer substrate semiconductor)	EPO; JPO; DERWENT	2003/05/30 16:32
-	-	0	c23c016\$.ipc. and (transfer\$4 with chamber with clean\$3 with (wafer substrate	USPAT; US-PGPUB	2003/05/30 16:36
-	-	12	chamber with clean\$3 with (wafer substrate	EPO; JPO; DERWENT	2003/05/30 16:36
-	-	91	semiconductor) ) (((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$4 with chamber with clean\$3 with (wafer	USPAT; US-PGPUB	2003/05/30 16:47
_	•		substrate semiconductor)) 5259881.URPN.	USPAT	2003/05/30 17:00
			("5228206"   "5972161"   "6143081"   "6178660"   "6204120"   "6232248").PN.	USPAT	2003/05/30 17:52
<u>-</u>			5972161.URPN. ("5240556"   "5344525"   "5554563"   "5670421"   "5830279").PN.	USPAT USPAT	2003/05/30 17:56 2003/05/30 17:58
-		37	transfer with chamber with ("HF" hydrofluoric)	USPAT; US-PGPUB	2003/05/30 18:12

	· <sub>I</sub>			
-	5	transfer with chamber with ("HF"	EPO; JPO;	2003/05/30 18:13
		hydrofluoric)	DERWENT	1
-	46	, · · · · · · · · · · · · · · · · · ·	USPAT;	2003/05/30 18:15
ű		US-6027960-\$ or US-5939333-\$ or	US-PGPUB;	
	,	US-5897710-\$ or US-5877086-\$ or	JPO;	
		US-5271732-\$ or US-5236868-\$ or	DERWENT	
		US-5202275-\$ .or US-6467491-\$ or		
		US-5981399-\$ or US-5551984 <b>-</b> \$ or	1	1
		US-4426439-\$ or US-6178660-\$ or		
		US-5972161-\$ or US-5695564-\$ or		
		US-4883020-\$ or US-5462397-\$ or		
	1	US-5474410-\$ or US-5527390-\$ or	Ī	·
		US-5740034-\$ or US-5609689-\$ or		
ĺ		US-5879461-\$ or US-5882165-\$ or		
		US-6143081-\$ or US-6528431-\$).did. or		
	1	(US-6140247-\$ or US-5043299-\$ or		1
		US-5259881-\$ or US-5294572-\$ or		
		US-6007675-\$ or US-6323463-\$ or		
		US-5770263-\$).did. or (US-20030053893-\$ or		
		US-20010050146-\$ or US-20010031556-\$ or		
İ		US-20010009813-\$ or US-20010001298-\$ or		
		US-20020034595-\$).did. or (JP-2000323425-\$		
9		or JP-2002270518-\$ or JP-09157073-\$ or		
	i `	JP-2002164408-\$).did. or (WO-200070666-\$		<del>!</del>
		or EP-430303-\$ or US-6007675-\$).did.		
-	18	((US-5766360-\$ or US-4816098-\$ or	USPAT;	2003/05/30 18:24
		US-6027960-\$ or US-5939333-\$ or	US-PGPUB	2003/03/30 10:24
	·	US-5897710-\$ or US-5877086-\$ or	00 10102	
		US-5271732-\$ or US-5236868-\$ or		
		US-5202275-\$ or US-6467491-\$ or		
		US-5981399-\$ or US-5551984-\$ or		
		US-4426439-\$ or US-6178660-\$ or		100
		US-5972161-\$ or US-5695564-\$ or		
		US-4883020-\$ or US-5462397-\$ or		
}		US-5474410-\$ or US-5527390-\$ or		
	٠.	US-5740034-\$ or US-5609689-\$ or		]
		US-5879461-\$ or US-5882165-\$ or		
1		US-6143081-\$ or US-6528431-\$).did. or		
		(US-6140247-\$ or US-5043299-\$ or	!	
		US-5259881-\$ or US-5294572-\$ or		
1		US-6007675-\$ or US-6323463-\$ or		
		US-5770263-\$).did. or (US-20030053893-\$ or		
		US-20010050146-\$ or US-20010031556-\$ or		
		US-20010009813-\$ or US-20010001298-\$ or		
	j	US-20020034595-\$).did. or (JP-2000323425-\$		
-00		or JP-2002270518-\$ or JP-09157073-\$ or		
]		JP-2002164408-\$).did. or (WO-200070666-\$		1
[		or EP-430303-\$ or US-6007675-\$).did.) and		
		(oxide with (remov\$3 clean\$3) with		
		chamber)		
L		CHARDEL)		

_	3	((00 0.00000 + 02 00 1020010 + 02	USPAT;	2003/05/30 18:24
		US-6027960-\$ or US-5939333-\$ or	US-PGPUB	
		US-5897710-\$ or US-5877086-\$ or		
		US-5271732-\$ or US-5236868-\$ or US-5202275-\$ or US-6467491-\$ or		
	- 10	US-5981399-\$ or US-5551984-\$ or		
		US-4426439-\$ or US-6178660-\$ or		
,		US-5972161-\$ or US-5695564-\$ or	,	
•		US-4883020-\$ or US-5462397-\$ or		
		US-5474410-\$ or US-5527390-\$ or		
		US-5740034-\$ or US-5609689-\$ or		
		US-5879461-\$ or US-5882165-\$ or		
		US-6143081-\$ or US-6528431-\$).did. or		
		(US-6140247-\$ or US-5043299-\$ or		Ì
		US-5259881-\$ or US-5294572-\$ or		·
		US-6007675-\$ or US-6323463-\$ or		
		US-5770263-\$).did. or (US-20030053893-\$ or US-20010050146-\$ or US-20010031556-\$ or		
		US-20010009813-\$ or US-20010001298-\$ or		]
		US-20020034595-\$).did. or (JP-2000323425-\$		
		or JP-2002270518-\$ or JP-09157073-\$ or		
		JP-2002164408-\$).did. or (WO-200070666-\$		
1.		or EP-430303-\$ or US-6007675-\$).did.) and		,
		(transfer\$3 same rotat\$3 same align\$3)		
-	0	( (odetee	EPO; JPO;	2003/06/02 08:30
	_	with plural\$3 with (even\$3))	DERWENT	
-	2	(	USPAT;	2003/06/02 08:22
1_	1716	plural\$3 with (even\$3))	US-PGPUB	2002/06/22 22 22
-	1715	((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.	USPAT; US-PGPUB	2003/06/02 08:23
_	0	i i i i i i i i i i i i i i i i i i i	USPAT;	2003/06/02 08:28
		multipl\$3) with even\$3)").PN.	US-PGPUB	2003/06/02 08:28
_	16		USPAT;	2003/06/02 08:27
		or (156/345.32)).CCLS.) and ((gas vapor)	US-PGPUB	2003,00,02 00.2,
		with (plural\$3 multipl\$3) with even\$3)		
-	145	(118/\$.ccls. 156/345.\$.ccls.) and ((gas	USPAT;	2003/06/02 08:28
		vapor) with (plural\$3 multipl\$3) with	US-PGPUB	
		even\$3)		
-	175	,	USPAT;	2003/06/02 08:28
		vapor) with (plural\$3 multipl\$3) with	US-PGPUB	1
		even\$3)		
-	0	/ ( / 400	EPO; JPO;	2003/06/02 08:30
		<pre>vapor) with (plural\$3 multipl\$3) with even\$3)</pre>	DERWENT	*
_	0	(c23c016\$.ipc. h011021\$.ipc.)and ((gas	EPO; JPO;	2003/06/02 08:29
		vapor) with (plural\$3 multipl\$3) with	DERWENT	2003/06/02 08:29
		(outlet inlet hole orifice))	· · · · · · · · · · · · · · · · · · ·	*
-	0		EPO; JPO;	2003/06/02 08:29
		vapor) same (plural\$3 multipl\$3) same	DERWENT	
		(outlet inlet hole orifice))		
_	0	'	EPO; JPO;	2003/06/02 08:29
		vapor) same (plural\$3 multipl\$3) same	DERWENT	'
	40150	(outlet inlet hole orifice))		0000100100
-	48150	c23c016\$.ipc.	EPO; JPO;	2003/06/02 08:30
_	742155	h011021\$.ipc.	DERWENT	2003/06/02 00-20
1	/42133	110110219.1pc.	EPO; JPO; DERWENT	2003/06/02 08:30
] -	0	(c23c016\$.ipc. h011021\$.ipc.) same (outlet	EPO; JPO;	2003/06/02 09:10
		with plural\$3 with (even\$3))	DERWENT	2003/00/02 09.10
-	5	(c23c016\$.ipc. h011021\$.ipc.) and (outlet	EPO; JPO;	2003/06/02 08:31
		<pre>with plural\$3 with (even\$3))</pre>	DERWENT	
-	82	(c23c016\$.ipc. h011021\$.ipc.)and ((gas	EPO; JPO;	2003/06/02 08:32
İ		vapor) with (plural\$3 multipl\$3) with	DERWENT	
	, ,	even\$3)		
<b>—</b> ,	70	118/\$.ccls. and (oxide with remov\$3)	EPO; JPO;	2003/06/02 09:11
_	607	110/6 gglo end /audda adda access 600	DERWENT	2002/20/20 22 11
_	667	118/\$.ccls. and (oxide with remov\$3)	USPAT;	2003/06/02 09:11
_	159	118/\$.ccls. and (oxide with remov\$3 with	US-PGPUB USPAT;	2003/06/02 09:12
	139	chamber)	US-PGPUB	2003/00/02 09:12
] -	27	118/\$.ccls. and (oxide with remov\$3 with	USPAT;	2003/06/02 09:13
		chamber with transfer\$4)	US-PGPUB	
	+			·

-	151	with (substrate wafer semiconductor) with	EPO; JPO; DERWENT	2003/11/20 13:49
_	624	<pre>(vapor\$4)) ((transfer\$4 transport\$4) with chamber with (substrate wafer semiconductor) with</pre>	USPAT; US-PGPUB	2003/11/20 13:38
-	68	<pre>(vapor\$4)) ("transfer chamber" with (substrate wafer semiconductor) with (vapor\$4))</pre>	USPAT; US-PGPUB	2003/11/20 13:38
_	17	((transfer\$4 adj chamber) with (substrate	EPO; JPO;	2003/11/20 14:26
_	0	<pre>wafer semiconductor) with (vapor\$4)) ("transfer\$4 chamber" with (vapor\$4))</pre>	DERWENT EPO; JPO; DERWENT	2003/11/20 14:01
-	161	("transfer chamber" with (vapor\$4))	USPAT; US-PGPUB	2003/11/20 14:21
-	37	<pre>("transfer chamber" with (vapor\$4) with (expos\$3 introduc\$3 inlet outlet supplied supply\$3))</pre>	USPAT; US-PGPUB	2003/11/20 14:04
_	124	(("transfer chamber" with (vapor\$4))) not (("transfer chamber" with (vapor\$4) with (expos\$3 introduc\$3 inlet outlet supplied supply\$3)))	USPAT; US-PGPUB	2003/11/20 14:21
-	1811	((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.	USPAT; US-PGPUB	2003/11/20 15:04
_	8	(vapor with (supply\$3 suppli\$3) with transfer\$4) and (((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.)	USPAT; US-PGPUB	2003/11/20 14:25
_	0	"vapor inlet" with "transfer chamber",	EPO; JPO; DERWENT	2003/11/20 14:27
_	0	"vapor inlet" with "transfer chamber"	USPAT; US-PGPUB	2003/11/20 14:27
_	1	"vapor port" with "transfer chamber"	USPAT; US-PGPUB	2003/11/20 14:27
	0	"vapor hole" with "transfer chamber"	USPAT; US-PGPUB	2003/11/20 14:27
	5	"vapor outlet" with "transfer chamber"	USPAT; US-PGPUB	2003/11/20 14:28
	3	<pre>(vapor\$4 adj (inlet hole port outlet conduit entrance introduc\$3 outlet aperture opening exit orifice vent\$3)) with "transfer chamber"</pre>	USPAT; US-PGPUB	2003/11/20 14:31
_	6	("4490209"   "5007982"   "5605603"   "5854137"   "5874362"   "6242350").PN.	USPAT	2003/11/20 14:32
_	6	<pre>(vapor\$4 with (inlet hole port outlet conduit entrance introduc\$3 outlet aperture opening exit orifice vent\$3)) with "transfer chamber"</pre>	EPO; JPO; DERWENT	2003/11/20 14:34
_	25		EPO; JPO; DERWENT	2003/11/20 14:41
<b>  -</b> 	32	427/335.ccls.	EPO; JPO; DERWENT	2003/11/20 14:42
<del>-</del>	3	427/335.ccls. and (transfer\$3 with chamber)	USPAT; US-PGPUB	2003/11/20 14:42
-	208	427/335.ccls.	USPAT; US-PGPUB	2003/11/20 14:45
	19	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (("hydrofluoric acid" "hf") with vapor\$4)	USPAT; US-PGPUB	2003/11/20 15:55
-	2	118/719.ccls. and imahashi.in.	USPAT; US-PGPUB	2003/11/20 15:00
-	0	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and ("transfer chamber" with (vaporiser vaporizer))	USPAT; US-PGPUB	2003/11/20 15:05
* -	0	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$3 with chamber with (vaporiser vaporizer))	USPAT; US-PGPUB	2003/11/20 15:07
-	10	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$3 with chamber with remov\$4 with oxide)	USPAT; US-PGPUB	2003/11/20 15:09

			· · · · · · · · · · · · · · · · · · ·	
-	39	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:09
•		or (156/345.32)).CCLS.) and (transfer\$3	US-PGPUB	
		with chamber with oxide)		
-	16		USPAT;	2003/11/20 15:14
		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
		chamber" with oxide)		1
_	92	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:18
		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
		chamber" with gas)		}
-	9	c23c016\$.ipc. and ("transfer chamber"	EPO; JPO;	2003/11/20 15:19
		with (remov\$3 clean\$3))	DERWENT	
_	79 -	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:49
		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
()		chamber" with (remov\$3 clean\$3))		
-	6	("5228206"   "5972161"   "6143081"	USPAT	2003/11/20 15:38
		"6178660"   "6204120"   "6232248").PN.		
-	3	5972161.URPN.	USPAT	2003/11/20 15:39
-	0	6467491.URPN.	USPAT	2003/11/20 15:39
-	13	("4795299"   "4917556"   "5228206"	USPAT	2003/11/20 15:42
		"5423971"   "5529657"   "5611861"		
		"5755938"   "5759334"   "5855675"		
		"5863170"   "5880924"   "5882165"		
		"5886864").PN.		
_	0	6467491.URPN.	USPAT	2003/11/20 15:43
*-	6	("5228206"   "5972161"   "6143081"	USPAT	2003/11/20 15:43
<b>,</b>		"6178660"   "6204120"   "6232248").PN.		
' - '	11	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:51
,		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
İ		chamber" with etch)	•	
-	0	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:52
ļ		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	1
Ì		chamber" with "pre-process")		
-	3	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:52
_	İ	or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
-		<pre>chamber" with "pre-processing")</pre>		
-	0	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:58
	İ	or (156/345.32)).CCLS.) and	US-PGPUB	
		(("hydrofluoric acid" "hf") with "transfer		
		chamber")		
-	195	118/\$.ccls. and (transfer\$4 with chamber	USPAT;	2003/11/20 15:59
		with expos\$4)	US-PGPUB	,, +-,
[	49	118/\$.ccls. and (transfer\$4 adj chamber	USPAT;	2003/11/20 15:59
		with expos\$4)	US-PGPUB	1111, 12, 20 20.09
-	49	118/\$.ccls. and ((transfer\$4 adj chamber)	USPAT;	2003/11/20 16:04
		with expos\$4)	US-PGPUB	
_	1	118/\$.ccls. and ((transfer\$4 adj chamber)	USPAT;	2003/11/20 16:04
1		with acid)	US-PGPUB	
- 1	1	("5043299").PN.	USPAT;	2003/11/21 10:55
	_ ]	,	US-PGPUB	2003/11/21 10:33
·-·	I		05 10105	

		T		
-	64	, , , , , , , , , , , , , , , , , , , ,	USPAT;	2003/11/21 13:22
		US-6528431-\$ or US-6140247-\$ or	US-PGPUB;	
		US-6027960-\$ or US-5939333-\$ or	JPO;	·
		US-5897710-\$ or US-5877086-\$ or	DERWENT	
		US-5271732-\$ or US-5236868-\$ or		
		US-5202275-\$ or US-5043299-\$ or		
		US-6467491-\$ or US-6083566-\$ or		
		US-5981399-\$ or US-5551984-\$ or		
		US-4883020-\$ or US-4426439-\$ or		
		US-6178660-\$ or US-6143081-\$ or		
•		US-5972161-\$ or US-5882165-\$ or		
		US-5695564-\$ or US-6183564-\$ or		
		US-5879461-\$ or US-5740034-\$).did. or		
		(US-5609689-\$ or US-5527390-\$ or		
		US-5474410-\$ or US-5462397-\$ or		
		US-6039811-\$ or US-6007675-\$ or		
		US-5294572-\$ or US-5259881-\$ or		1
1		US-6323463-\$ or US-5770263-\$ or		
		US-4565157-\$ or US-4262631-\$ or		•
	İ	US-5314574-\$ or US-6578589-\$ or		_
		US-6221742-\$ or US-6132564-\$ or		
		US-6358859-\$ or US-4386119-\$ or		
		US-4834020-\$).did. or (US-20030053893-\$ or		
		US-20010031556-\$ or US-20010009813-\$ or		
		US-20010001298-\$ or US-20010050146-\$ or		
-		US-20020034595-\$ or US-20020069899-\$ or	ļ	
•		US-20020020429-\$ or US-20010017103-\$ or		
		US-20020184896-\$).did. or (JP-2000323425-\$		
	Ì	or JP-2002270518-\$ or JP-09157073-\$ or		
!		JP-2002164408-\$ or JP-61054628-\$).did. or	}	
		(WO-200070666-\$ or US-6007675-\$ or		
		EP-430303-\$ or US-20010031556-\$).did.		· ·
-	291	(427/\$.ccls. 438/\$.ccls.) and (transfer\$4	USPAT;	2003/11/21 11:03
		with chamber with vapor\$4)	US-PGPUB;	
			JPO;	
			DERWENT	
_	38	(427/\$.ccls. 438/\$.ccls.) and ((transfer\$4	USPAT;	2003/11/21 11:03
		adj chamber) with vapor\$4)	US-PGPUB;	2003/11/21 11:03
		aug similisty with vupory ly	JPO;	
			DERWENT	
_	- 40	(427/\$.ccls. 438/\$.ccls.) and ((transfer\$4	USPAT;	2003/11/21 11:19
		adj chamber) with (vapor\$4 "hf"	US-PGPUB;	2003/11/21 11.19
		"hydrofluoric" "hydrogen fluoride"))	JPO;	
		maragem rideriae //	DERWENT	*
_	6	("4490209"   "5007982"   "5605603"	USPAT	2003/11/21 11:11
	1	"5854137"   "5874362"   "6242350").PN.	JULIAI	5000/11/51 11·11
_	1	(427/\$.ccls. 438/\$.ccls.) and ((transfer\$4	USPAT;	2003/11/21 11:21
		adj chamber) with ("etching gas"))	US-PGPUB;	~000/it/~t it:~T
		Conting gas //	JPO;	
	<b>]</b>		DERWENT	
_	1	(427/\$.ccls. 438/\$.ccls.) and ((transfer\$4	USPAT;	2003/11/21 11:23
	[ -	adj chamber) with (etch\$3 with (while	US-PGPUB	2000/II/CI II.CO
		during)))	OD LOLOD	•
_	25		USPAT;	2003/11/21 11:24
		adj chamber) with (remov\$3 with (layer	US-PGPUB	2005/11/21 11.24
		film coating)))	05 10105	
_	8	(118/715-733.ccls. 156/345.\$.ccls.) and	USPAT;	2003/11/21 11:29
		((transfer\$4 adj chamber) with (remov\$3	US-PGPUB	2003/11/21 11:29
	]	with (layer film coating)))	ON EGEOD	
<b> </b>	44	5314574.URPN.	USPAT	2003/11/21 11:39
_	4	("4654106"   "4857142"   "5169408"	USPAT	2003/11/21 11:39
	"	"5248380").PN.	USEMI	2003/11/21 11:49
_	0	"09758610"	USPAT;	2003/11/21 12:37
		03,00010	US-PGPUB	2003/11/21 12:3/
_	1	"09/758,610"	USPAT;	2003/11/21 12:41
		0.5/ 1.50/ 010	USPAT; US-PGPUB	2003/11/21 12:41
_	1	("6178660").PN.	USPAT;	2003/11/21 12:41
		( OI.0000 ).LW.	· ·	2003/11/21 12:41
<u> </u>	L		US-PGPUB	

2 ((US-5766360-5 or US-616098-\$ or US-628431-6 or US-6023760-5 or US-602376-6 or US-602381-5 or US-602678-7 or US-602381-5 or US-602678-7 or US-602678-8 or US-602678-7 or US-602678-8 o					
US-602730-0-3 or US-593333-5 or US-5203660-4 or US-5273732-5 or US-5203660-4 or US-5273732-5 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-5203660-4 or US-520360-4 or US-520360-4 or US-520360-4 or US-520360-4 or US-520360-4 or US-520360-4 or US-520360-4 or US-520360-3 or US	-	2	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2003/11/21 14:02
US-589710-S or US-5877086-S or US-5872087-S or US-5020275-S or US-5020229-S or US-502020-S or US-502029-S or US-502020-S or US-502029-S or US-502020-S or US-502029-S or US-50202020-S S or US-5020202029-S or US-50202029-S or US-50202029-S or US-5020202029-S or US-50202029-S or US-5020202029-S or US-50202029-S o			• • • • • • • • • • • • • • • • • • • •	US-PGPUB;	
US-5271732-\$ or US-5236686-\$ or US-52278669-\$ or US-502277-\$ or US-503398-\$ or US-502277-\$ or US-503398-\$ or US-56467491-\$ or US-503398-\$ or US-56298199-\$ or US-562981-\$ or US-5629819-\$ or US-562981-				-	
US-5202279-6 or US-5013299-5 or US-5013299-5 or US-501399-7 or US-501399-7 or US-551984.5 or US-551984.5 or US-551984.5 or US-551984.5 or US-551984.5 or US-551984.5 or US-551984.5 or US-51984.5 or US-51984.5 or US-51988.5 or			•	DERWENT	
US-6467491-8 or US-6083566-3 or US-486020-8 or US-426439-5 or US-4426439-5 or US-4572161-8 or US-5572161-8 or US-5572161-8 or US-5672161-8 or US-5673618-8 or US-572161-8 or US-5872161-8 or US-5872161-8 or US-5872163-8 or US-572161-8 or US-5872163-9 or US-572161-8 or US-5872163-9 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-5721637-8 or US-2002001288-9 or US-2002001399-8 or US-2002001288-9 or US-2002001399-8 or US-2002001499-8 or US-2002001399-8 or US-2002001499-8 or US-2002001399-8 or US-2002001499-8 or US-2002001399-8 or US-2002001499-8 or US-2002001399-8 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001499-9 or US-2002001					
US-5981399-\$ or US-55813984-\$ or US-5813984-\$ or US-6173660-\$ or US-6143081-\$ or US-6173660-\$ or US-6143081-\$ or US-5891564-\$ or US-5891564-\$ or US-5892164-\$ or US-612739-\$ or US-627372-\$ or US-627398-\$ or US-6273401-\$ or US-623463-\$ or US-6127568-\$ or US-627468-\$ or US-623463-\$ or US-623463-\$ or US-623463-\$ or US-623463-\$ or US-623463-\$ or US-62312564-\$ or US-6230303393-\$ or US-62010031536-\$ or US-62010039813-\$ or US-62010039813-\$ or US-6200003839-\$ or US-62010039813-\$ or US-6200003455-\$ or US-62000038393-\$ or US-2001001288-\$ or US-62000038393-\$ or US-2001001288-\$ or US-62000038393-\$ or US-2001001288-\$ or US-200100039813-\$ or US-200200435-\$ or US-200100039813-\$ or US-200200435-\$ or US-200100039813-\$ or US-200200435-\$ or US-200100039813-\$ or US-200200435-\$ or US-200100039813-\$ or US-200200435-\$ or US-200100039813-\$ or US-200200435-\$ or US-200100039813-\$ or US-200200435-\$ or US-200100039813-\$ or US-200200435-\$ or US-200100039813-\$ or US-200200435-\$ or US-20010039813-\$ or US-200200435-\$ or US-20010039813-\$ or US-2002003981-\$ or US-200			· · · · · · · · · · · · · · · · · · ·		
US-4883020-% or US-4426439-% or US-617660-9 or US-617660-1 or US-617660-8 or US-618361-% or US-587361-% or US-587361-% or US-587361-% or US-587361-% or US-587361-% or US-587361-% or US-5764034-%, did. or US-587361-% or US-57764034-9, did. or US-5609889-% or US-5273390-% or US-5273390-% or US-5273390-% or US-5273390-% or US-5273390-% or US-5273390-% or US-5273457-% or US-607673-% or US-607673-% or US-627463-% or US-5776739-% or US-633889-% or US-4386119-% or US-633889-% or US-4386119-% or US-633889-% or US-2001003156-% or US-2001003156-% or US-2001003156-% or US-2001003156-% or US-2002002479-% or US-20010051046-% or US-2002002479-% or US-20010017103-% or US-2002002479-% or US-20010017103-% or US-2002002479-% or US-20010017103-% or US-2002002479-% or US-200100757-% or US-2002002479-% or US-200100757-% or US-2002002479-% or US-200100757-% or US-2002002479-% or US-200100757-% or US-2002002479-% or US-200100757-% or US-2002002479-% o			· · · · · · · · · · · · · · · · · · ·		1
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US-5972161-\$ or US-5882165-\$ or   US-589564-\$ or   US-589564-\$ or   US-589564-\$ or   US-589564-\$ or   US-589564-\$ or   US-595604-\$ or   US-59740034-\$), d.d. or   US-5695668-\$ or   US-5602391-\$ or   US-50462391-\$ or   US-50462391-\$ or   US-5249372-\$ or   US-5259891-\$ or   US-523467-\$ or   US-523467-\$ or   US-523467-\$ or   US-623467-\$ or   US-636859-\$ or   US-62147-\$ or   US-636859-\$ or   US-2001000518-\$ or   US-2001000518-\$ or   US-2001000518-\$ or   US-2001000518-\$ or   US-2001000518-\$ or   US-20020006899-\$ or   US-20020006999-\$ or   US-20020006999-\$ or   US-20020006999-\$ or   US-20020006999-\$ or   US-20020006999-\$ or   US-20020018896-\$), did. or   (US-2003005345-\$ or   US-20020006999-\$ or   US-20020018896-\$), did. or   (US-2003005345-\$ or   US-20020006999-\$ or   US-20020018896-\$), did. or   (US-2003005345-\$ or   US-20020006999-\$ or   US-20020018896-\$), did. or   (US-2003005345-\$ or   US-20020006999-\$ or   US-20020018896-\$), did. or   (US-2003005345-\$ or   US-20020006999-\$ or   US-20020018896-\$), did. or   (US-2003005346-\$ or   US-20020006999-\$ or   US-20020018896-\$), did. or   (US-2003005346-\$ or   US-20020006999-\$ or   US-2002000699-\$ or   US-2002000699-\$ or   US-2002000699-\$ or   US-2002000699-\$ or   US-2002000699-\$ or   US-2002000699-\$ or   US-200200699-\$ or			US-4883020-\$ or US-4426439-\$ or		
US-569564-\$ or US-5610303-\$), idd. or   US-5879661-\$ or US-5527390-\$ or US-5627390-\$ or US-6039811-\$ or US-6039811-\$ or US-603981-\$ or US-6039811-\$ or US-603981-\$ or US-603981-\$ or US-603981-\$ or US-603981-\$ or US-6038403-\$ or US-5627398-\$ or US-6328403-\$ or US-678598-\$ or US-6221422-\$ or US-678598-\$ or US-6221422-\$ or US-678598-\$ or US-6221422-\$ or US-678598-\$ or US-6038859-\$ or US-638859-\$ or US-2001003981-\$ or US-2001000128-\$ or US-20010032445-\$ or US-2001003116-\$ or US-2002020429-\$ or US-20010032445-\$ or US-2002032425-\$ or US-20020313556-\$ loid. or (WO-200070666-\$ or US-20010031556-\$ loid.) and (transfer with chamber with aliqn)   USFAT; U		İ	US-6178660-\$ or US-6143081-\$ or		
US-5809461-% or US-5940034-8),did. or	İ		US-5972161-\$ or US-5882165-\$ or		
US-5809461-% or US-5940034-8),did. or			US-5695564-\$ or US-6183564-\$ or		
(US-5609689-S or US-5527390-S or US-6039611-\$ or US-6039611-\$ or US-6007675-\$ or US-6234572-\$ or US-5294572-\$ or US-5294572-\$ or US-5294572-\$ or US-5294572-\$ or US-5294572-\$ or US-6036819-\$ or US-632463-\$ or US-632631-\$ or US-632631-\$ or US-632635-\$ or US-638689-\$ or US-4386619-\$ or US-4286619-\$ or US-20010003155-\$ or US-20010003155-\$ or US-20010003155-\$ or US-20010003155-\$ or US-20010003155-\$ or US-2002003495-\$ or US-20020003495-\$ or US-2002003495-\$ or US-20020003495-\$ or US-200200032342-\$ or US-200200069899-\$ or US-2002000492-\$ or US-200200032342-\$ or US-2002000391-\$ or US-20020003495-\$ or US-200200032342-\$ or US-20020003993-\$ or US-2002000393-\$ or US-200200032342-\$ or US-2002000393-\$ or US-20020003355-\$ or US-200200032342-\$ or US-2002000393-\$ or US-200200033-\$ or US-20020003355-\$ or US-20020003345-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-200200033-\$ or US-2001003155-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-200200033-\$ or US-20020033-\$ or US-200200033-\$ or US-200			US-5879461-\$ or US-5740034-\$).did. or		
US-647410-% or US-5462397-% or US-603981-% or US-603981-% or US-603981-% or US-6052467-% or US-5259881-% or US-6323467-% or US-6259881-% or US-6323467-% or US-625898-% or US-6323658-% or US-625742-% or US-625898-% or US-625742-% or US-625898-% or US-625742-% or US-6132564-% or US-627142-% or US-6132564-% or US-627142-% or US-6132564-% or US-2001000381-% or US-2001000128-% or US-2001000381-% or US-2001000128-% or US-2001000381-% or US-2002004048-% or US-2001000381-% or US-2002004048-% or US-2001000381-% or US-2002004048-% or US-2001000381-% or US-2002004048-% or US-2001000381-% or US-2002004048-% or US-2001000381-% or US-2002004048-% or US-2001000381-% or US-2002004048-% or US-200200548-% or US-2001000381-% or US-2002004048-% or US-200200548-% or US-2001000381-% or US-200200548-% or US-2001000381-% or US-200200548-% or US-20020					
US-6039911-6 or US-6007675-8 or US-5224572-5 or US-52245801-8 or US-6224631-8 or US-5224575-5 or US-5252631-8 or US-5324574-5 or US-5770263-8 or US-5314574-5 or US-6578589-8 or US-6221742-5 or US-6578589-8 or US-6221742-5 or US-6378589-5 or US-638859-5 or US-638859-5 or US-20010031556-5 or US-20010031556-6 or US-20010031556-8 or US-20010009813-8 or US-20020034395-5 or US-20010009813-8 or US-20020034395-5 or US-2001000103-8 or US-2002003499-8 or US-2002003499-5 or US-2002003495-5 or US-2002005899-3 or US-2002003495-5 or US-2001003103-8 or US-200200408496-9).did. or (GP-2000323425-9 or JP-20022164408-8 or JP-09157073-8 or JP-20022164408-8 or JP-09157073-8 or US-20020034025-9 or EP-430303-5 or US-20010031556-5).did.) and (transfer with chamber with align)  -					
US-5294572-\$ or US-5259881-\$ or US-623463-\$ or US-456157-\$ or US-4262631-\$ or US-45157-\$ or US-5259881-\$ or US-45157-\$ or US-622742-\$ or US-635885-\$ or US-635885-\$ or US-635885-\$ or US-635885-\$ or US-20010005813-\$ or US-20201001298-\$ or US-202010001298-\$ or US-2020200202429-\$ or US-202020202429-\$ or US-202020202429-\$ or US-202020202429-\$ or US-2020202698-\$ or US-2020202698-\$ or US-2020202698-\$ or US-2020202699-\$ or US-2020206989-\$ or US-2020206999-\$ or US-202020698-\$ or US-202020698-\$ or US-202020699-\$ or US-202020669-\$ or US-6007675-\$ or EP-430903-\$ or US-202020698-\$ or US-2020206999-\$ or US-202020699-\$ or US-2020206999-\$ or US-202020698-\$ or US-2020206999-\$ or US-202020699-\$ or US-2020206999-\$ or US-2020206999-\$ or US-2020206999-\$ or US-2020206999-\$ or US-2020206999-\$ or US-2020206999-\$ or US-2020206999-\$ or US-2020206999-\$ or US-202020699-\$ or US-202020699-\$ or US-202020699-\$ or US-202020699-\$ or US-202020699-\$ or US-202020699-\$ or US-202020699-\$ or US-202020699-\$ or US-202020699-\$					
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US-5314574-3 or US-678589-3 or US-6227472-3 or US-6132564-5 or US-62318619-5 or US-62318619-5 or US-20300053893-\$ or US-20300031556-5 or US-20010031556-5 or US-2001003146-5 or US-20020020129-8 or US-2002006899-5 or US-202002018495-5 or US-202002018495-5 or US-202002018495-5 or US-202002018495-5 or US-202002018495-5 or US-202002018495-5 or US-202002018495-5 or US-202001703-8 or US-202018408-5 or US-202001703-8 or US-202018408-5 or US-202018495-5 or US-202018408-5 or US-20201					1
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US-20010001298-\$ or US-20010050146-\$ or US-20020034595-\$ or US-20020034595-\$ or US-20020034595-\$ or US-20020034595-\$ or US-20010017103-\$ or US-2002014896-\$, did. or (P-200323425-\$ or JP-200270518-\$ or JP-09157073-\$ or JP-200270518-\$ or JP-09157073-\$ or JP-200270518-\$ or JP-09157073-\$ or EP-430303-\$ or US-20010031556-\$).did.) and (transfer with chamber with align)  - 0 pas-sylvia.in.  - 1 pas-sylvia-h.in.  - 29 pas-sylvia-\$.in.  - 3 pas-sylvia-\$.in.  - 3 pas-sylvia-\$.in.  - 4 ("6391148").PN.  - 29 ("transfer chamber" "transferring chamber") with vapor\$3 ("transfer chamber" "transferring chamber") with vapor\$3 und (substrate wafer semiconductor)  - 117 ("("transfer chamber" "transferring chamber") with vapor\$3) and (substrate wafer semiconductor)  - 117 ("("transfer chamber" "transferring chamber") with vapor\$3) and (substrate wafer workpiece semiconductor)  - 118 ("(vapor\$3 with solution) bubbler) with (transfer\$3 adj chamber)) and (1414%.ccls.)  - 8 (("vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  - 1 (("vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  - 1 (("vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber)) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate wafer) and (substrate) and (substrate wafer) and (substrate) and (substrate wafer) and (substrate) and (sub					
US-20020034595-9 or US-20020069899-9 or US-2002012429-9 or US-2001017103-8 or US-200201249896-9).did. or (JP-200323425-9 or JP-2002184896-9).did. or (JP-200323425-9 or JP-2002164408-8 or JP-61054628-9).did. or (WO-200070666-8 or US-6007675-8 or EP-430303-8 or US-20010031556-9).did.) and (transfer with chamber with align)  - 0 pas-sylvia-in.  1 pas-sylvia-hin.  3 pas-sylvia-hin.  4 ("6391148").FN.  1 ("6391148").FN.  2 ("transfer chamber" "transferring chamber") with vapor\$3  116 ("transfer chamber" "transferring chamber") with vapor\$3  116 ("transfer chamber" "transferring chamber") with vapor\$3 and (substrate wafer semiconductor)  1 (("vapor\$3 with solution) bubbler) with (transfer\$3 adj chamber) with (transfer\$3 adj chamber) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber)) and (substrate wafer\$7 per ((solution)) bubbler) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  1 (((solution)) with (transfer\$4 adj chamber))  2 (((solution)) with (transfer\$4 adj chamber))  3 (((solution)) with (transfer\$4 adj chamber))  4 (((solution)) with (transfer\$4 adj chamber))  5 (((solution)) with (transfer\$4 adj chamber))  6 (((solution)) with (transfer\$4 adj chamber))  7 (((solution)) with (transfer\$4 adj chamber))  8 (((solution)) with (transfer\$4 adj chamber))  9 (((solution)) with (transfer\$4 adj chamber))  10 (((solution)) with (transfer\$4 adj chamber))  110 (((solution)) with (transfer\$4 adj chamber))  111 ((solution)) with (transfer\$4 adj chamber))  112 ((solution)) with (transfer\$4 adj chamber))  113 ((solution)) with (transfer\$4 adj chamber))  114 ((solution)) with (transfer\$4 adj c	ļ				<b> </b>
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US-20/20/18/49/6-\$).did. or (JP-20103/23/425-\$ or JP-20/22/16/44/8-\$ or JP-61/54/628-\$).did. or UF-20/20/16/44/8-\$ or JP-61/54/628-\$).did. or UF-20/20/16/44/8-\$ or JP-61/54/628-\$).did. or UF-20/20/16/44/8-\$ or JP-61/54/628-\$).did. or UF-20/20/16/44/8-\$ or JP-61/54/628-\$).did. or UF-20/20/20/66/6-\$ or US-600/67/5-\$ or EF-43/30/3-\$ or US-20/20/10/31556-\$).did.) and (transfer with chamber with align) US-FGPUB; JPO; DERWENT US-FGPUB US-PAT; US-PGPUB US-P				ļ	1
Or JP-200270518-\$ or JP-09157073-\$ or JP-200270666-\$ or US-6007675-\$ or EP-430303-\$ or US-2001031556-\$).did. or (W0-200070666-\$ or US-6007675-\$ or EP-430303-\$ or US-2001031556-\$).did.) and (transfer with chamber with align)					
JP-2002164408-\$ or JP-61054628-\$, did. or (Wo-200070666-\$ or US-6007675-\$ or US-6007675-\$ or EP-430303-\$ or US-20010031556-\$).did.) and (transfer with chamber with align)					
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EP-430303-\$ or US-20010031556-\$).did.) and (transfer with chamber with align)					
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116	-	1/4			2004/05/04 12:00
Chamber") with vapor\$3) and (substrate wafer semiconductor)   (("transfer chamber" "transferring chamber") with vapor\$3) and (substrate wafer workpiece semiconductor)   (((vapor\$3 with solution) bubbler) with (transfer\$3 adj chamber)) and (414/\$.ccls. US-PGPUB	1	444	l •		
Wafer semiconductor	-	116	' '	•	2004/05/04 12:02
117				US-PGPUB	]
Chamber") with vapor\$3) and (substrate wafer workpiece semiconductor)   Compose wafer workpiece semiconductor)	ļ		, , , , , , , , , , , , , , , , , , ,		
wafer workpiece semiconductor)		117	, , , , , , , , , , , , , , , , , , ,	·	2004/05/04 12:03
0 (((vapor\$3 with solution) bubbler) with (transfer\$3 adj chamber)) and (414/\$.ccls. US-PGPUB 118/\$.ccls. 216/\$.ccls. 427/\$.ccls.)  8 (((vapor\$3 with solution) bubbler) with (transfer\$3 adj chamber)) USPAT; US-PGPUB ((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber)) USPAT; US-PGPUB US-PGPUB US				US-PGPUB	
(transfer\$3 adj chamber)) and (414/\$.ccls. US-PGPUB  118/\$.ccls. 216/\$.ccls. 427/\$.ccls.)  (((vapor\$3 with solution) bubbler) with (transfer\$3 adj chamber))  (((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  (((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  (((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  (((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  (((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  ((((solution)) with (transfer\$4 adj EPO; JPO; 2004/05/04 12:10 DERWENT  (((solution)) with (transfer\$4 adj EPO; JPO; 2004/05/04 12:28 DERWENT  semiconductor)  ((gas\$4 with (transfer\$4 adj chamber)) and EPO; JPO; 2004/05/04 12:11					
118/\$.ccls. 216/\$.ccls. 427/\$.ccls.)   (((vapor\$3 with solution) bubbler) with (transfer\$3 adj chamber))   (((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with solution) bubbler) with (transfer\$4 adj berwent)   ((vapor\$3 with so	-	0	(((vapor\$3 with solution) bubbler) with		2004/05/04 12:05
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(transfer\$4 adj chamber))  ((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  ((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  ((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  ((solution)) with (transfer\$4 adj berwent  ((solution)) with (transfer\$4 adj berwent  ((solution)) with (transfer\$4 adj berwent  ((solution)) with (transfer\$4 adj berwent  ((solution)) with (transfer\$4 adj berwent  ((solution)) with (transfer\$4 adj berwent  ((solution)) and (substrate workpiece wafer semiconductor)  (gas\$4 with (transfer\$4 adj chamber)) and bero; JPO; 2004/05/04 12:11	,	_			
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(transfer\$4 adj chamber))  (((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  ((( solution)) with (transfer\$4 adj chamber))  ((( solution)) with (transfer\$4 adj chamber))  ((( solution)) with (transfer\$4 adj chamber)) and (substrate workpiece wafer semiconductor)  (gas\$4 with (transfer\$4 adj chamber)) and EPO; JPO; 2004/05/04 12:11		<u> </u>			
4 (((vapor\$3 with solution) bubbler) with (transfer\$4 adj chamber))  180 (((solution)) with (transfer\$4 adj chamber))  116 (((solution)) with (transfer\$4 adj chamber)) and (substrate workpiece wafer semiconductor)  127 (gas\$4 with (transfer\$4 adj chamber)) and EPO; JPO; 2004/05/04 12:11	-	[ 8 ]			2004/05/04 12:08
(transfer\$4 adj chamber))  180 (((solution)) with (transfer\$4 adj chamber))  116 (((solution)) with (transfer\$4 adj chamber)) and (substrate workpiece wafer semiconductor)  127 (gas\$4 with (transfer\$4 adj chamber)) and EPO; JPO; 2004/05/04 12:11					1
180 ((( solution)) with (transfer\$4 adj chamber))  116 ((( solution)) with (transfer\$4 adj chamber) and (substrate workpiece wafer semiconductor)  127 (gas\$4 with (transfer\$4 adj chamber)) and EPO; JPO; 2004/05/04 12:11	<del></del>	4		· ·	2004/05/04 12:10
chamber))  116 (((solution)) with (transfer\$4 adj			_ ' '	DERWENT	1
116 (((solution)) with (transfer\$4 adj chamber)) and (substrate workpiece wafer semiconductor)  127 (gas\$4 with (transfer\$4 adj chamber)) and EPO; JPO; 2004/05/04 12:11	-	180		EPO; JPO;	2004/05/04 12:10
chamber)) and (substrate workpiece wafer semiconductor)  127 (gas\$4 with (transfer\$4 adj chamber)) and EPO; JPO; 2004/05/04 12:11			, ,	DERWENT	
semiconductor)	<b>–</b>	116		EPO; JPO;	2004/05/04 12:28
127 (gas\$4 with (transfer\$4 adj chamber)) and EPO; JPO; 2004/05/04 12:11				DERWENT	
			somi conductor)		
(substrate workpiece wafer semiconductor)   DERWENT			·	ı	
	_	127	(gas\$4 with (transfer\$4 adj chamber)) and		2004/05/04 12:11

-	14	(gas\$4 with solution with (transfer\$4 adj chamber)) and (substrate workpiece wafer semiconductor)	EPO; JPO; DERWENT	2004/05/04 12:27
-	0	(gas\$4 with solution with (transfer\$4 adj chamber)) and (substrate workpiece wafer	USPAT; US-PGPUB	2004/05/04 12:15
_	37	and (substrate workpiece wafer	USPAT; US-PGPUB	2004/05/04 12:16
-	I	semiconductor) 5983909.URPN.	USPAT	2004/05/04 12:19
-	3 4	("5599438"   "5616221"   "5635053"	USPAT USPAT	2004/05/04 12:19 2004/05/04 12:19
_	11	"5676760").PN. 6039815.URPN.	USPAT	2004/05/04 12:20
-	6	("5190627"   "5599438"   "5616221"   "5635053"   "5676760"   "5806126").PN.	USPAT	2004/05/04 12:21
-	0	"vaporous solution"	EPO; JPO; DERWENT	2004/05/04 12:27
_	0	(bubbler with (transfer\$4 adj chamber)) and (substrate workpiece wafer	EPO; JPO; DERWENT	2004/05/04 12:29
-	1	semiconductor) (bubbler with (transfer\$4 adj chamber)) and (substrate workpiece wafer semiconductor)	USPAT; US-PGPUB	2004/05/04 12:28
-	0	· ·	EPO; JPO; DERWENT	2004/05/04 12:30
-	1		EPO; JPO; DERWENT	2004/05/04 12:31
-	5	· ·	USPAT; US-PGPUB	2004/05/04 12:32
_	0	· · · · · · · · · · · · · · · · · · ·	EPO; JPO; DERWENT	2004/05/04 12:33
<b>-</b>	4	( (transfer\$4 adj chamber) with vapor with (liquid aqueous)) and (substrate workpiece wafer semiconductor)	USPAT; US-PGPUB	2004/05/04 12:34
-	195	<pre>( ((transfer\$4 transport\$3) with chamber) with vapor with (liquid aqueous)) and (substrate workpiece wafer semiconductor)</pre>	USPAT; US-PGPUB	2004/05/04 13:24
	397	<pre>( ((transfer\$4 transport\$3) adj chamber) with (clean\$3)) and (substrate workpiece wafer semiconductor)</pre>	USPAT; US-PGPUB	2004/05/04 13:25
-	. 8	( ((transfer\$4 transport\$3) adj chamber) with (clean\$3) with vapor\$3) and (substrate workpiece wafer semiconductor)	USPAT; US-PGPUB	2004/05/04 13:28
_	397	<pre>( ((transfer\$4 transport\$3) adj chamber) with (clean\$3) ) and (substrate workpiece wafer semiconductor)</pre>	USPAT; US-PGPUB	2004/05/04 13:28
-	45	5314574.URPN.	USPAT	2004/05/04 13:31
_	116	(156/345.31.ccls. 156/345.32.ccls. 414/935-939.ccls. 118/719.ccls.	USPAT; US-PGPUB	2004/05/04 14:48
		204/298.25.ccls. 204/298.26.ccls. 204/298.35.ccls.) and (((transfer\$4 transport\$3) adj chamber) same (solution		-
_	764	aqueous liquid vapor\$3)) "hf vapor"	USPAT;	2004/05/04 14:48
_	34	"hf vapor" and ((transfer\$4 transport\$3)	US-PGPUB US-PAT;	2004/05/04 14:48
_	0	adj chamber) "hbr vapor" and ((transfer\$4 transport\$3)	US-PGPUB USPAT;	2004/05/04 14:48
_	0	adj chamber)  ("hbr vapor" "hbr vapor" "hcl vapor") with	US-PGPUB USPAT;	2004/05/04 14:48
_	3	((transfer\$4 transport\$3) adj chamber) ("hbr vapor" "hbr vapor" "hcl vapor") with	US-PGPUB USPAT;	2004/05/04 14:49
_		(transfer\$4 transport\$3) with chamber ("hbr vapor" "hbr vapor" "hcl vapor") with	US-PGPUB EPO; JPO;	2004/05/04 14:52
_	5	(transfer\$4 transport\$3) with chamber ("hbr" "hbr" "hcl") with vapor with	DERWENT USPAT;	2004/05/04 14:52
		(transfer\$4 transport\$3) with chamber	US-PGPUB	2007/03/04 14:33

-	5				
	5	'	USPAT;	2004/05/04 1	14:56
•		(transfer\$4 transport\$3) with chamber	US-PGPUB		
-	6	1 ( 1 000.502 )	USPAT	2004/05/04 1	14:55
		"5854137"   "5874362"   "6242350").PN.			
-	1	("hbr" "hbr" "hcl") with vapor\$5 with	EPO; JPO;	2004/05/04 1	14.57
		(transfer\$4 transport\$3) with chamber	DERWENT	2001,00,01	
_	8	(acid\$2) with vapor\$5 with (transfer\$4	EPO; JPO;	2004/05/04 1	15.05
	•	transport\$3) with chamber	DERWENT	2004/03/04 1	13:03
_	28	(acid\$2) with vapor\$5 with (transfer\$4		2004/05/04 1	5.40
	20	transport\$3) with chamber	USPAT; US-PGPUB	2004/05/04 1	13:43
l <u> </u>	404	kondo.in. and oxide and vapor		0004/05/04 7	
	404	kondo.in. and oxide and vapor	USPAT;	2004/05/04 1	15:43
	83	James de la la la la la la la la la la la la la	US-PGPUB		
	0.3	kondo.in. and oxide and vapor	EPO; JPO;	2004/05/04 1	.5:43
	4.5		DERWENT		
-	47	kondo.in. and oxide and vapor and	EPO; JPO;	2004/05/04 1	.5:44
	_	(substrate wafer semiconductor workpiece)	DERWENT		
-	8	kondo.in. and oxide and vapor and	EPO; JPO;	2004/05/04 1	5:49
		(substrate wafer semiconductor workpiece)	DERWENT		
		and acid\$3			
-	182	kondo.in. and oxide and vapor and	USPAT;	2004/05/04 1	5:49
		(substrate wafer semiconductor workpiece)	US-PGPUB		
	ļ	and acid\$3			
-	4	kondo.in. and (oxide same vapor same	USPAT;	2004/05/04 1	5.50
		(substrate wafer semiconductor workpiece)	US-PGPUB	2004/03/04 1	3.32
		same acid\$3)	OB TOTOE		
_	43	5303671.URPN.	USPAT	2004/05/04 1	C. C1
_	1	"4592306".PN.	USPAT	2004/05/04 1	
_	ōl	(("hbr vapor" "hbr vapor" "hcl vapor")	USPAT;	2004/05/04 1	
	-	with (transfer\$4 transport\$3) with	US-PGPUB	2004/05/04   1.	5:55
1		chamber) and (vapor\$3 same acid\$3)	US-FGFUB		
_	0	(("hbr vapor" "hbr vapor" "hcl vapor")	I II O D A III .	0004/05/04 1	
	Ĭ	with (transfer\$4 transport\$3) with	USPAT;	2004/05/04 1	5:52
		chamber) and (acid\$3)	US-PGPUB		
_	0				[
	١	((("hbr vapor" "hbr vapor" "hcl vapor")	USPAT;	2004/05/04 1	5:52
	ļ	with (transfer\$4 transport\$3) with	US-PGPUB		-
		chamber) and (vapor\$3 same acid\$3)) and (		,	
	_	vapor\$3 same acid\$3)			
_	2	5303671.URPN. and ( vapor\$3 same acid\$3)	USPAT;	2004/05/04 1	5:53
		5000 CT1	US-PGPUB		
_	7	5303671.URPN. and ( acid\$3)	USPAT;	2004/05/04 15	5:55
0)(0	. [	5000 684	US-PGPUB		
-	18	5303671.URPN. and (vapor\$3)	USPAT;	2004/05/04 15	5:56
			US-PGPUB		
-	2	5303671.URPN. and (vapor\$3 with	USPAT;	2004/05/04 17	7:00 l
		(transfer\$4 transport\$4))	US-PGPUB	_	-
-	1	"4592306".PN.	USPAT	2004/05/04 16	6:10
-	43	5303671.URPN.	USPAT	2004/05/04 16	
-   ,	1	10/265,899	USPAT;	2004/05/04 17	
	1		US-PGPUB	_001/00/04 I	
-	1	10/265,699	USPAT;	2004/05/04 17	7.01
		·	US-PGPUB	2003/00/04 I	, . o <sub>1</sub>
_	1	414/936.ccls. and (vapor\$3 with (acid "HF"	USPAT;	2004/05/05 12	2.16
	_	"Hbr" "HCL"))	US-PGPUB	2004/03/03 12	7:10
_	I	5474641.URPN.		2004/05/05 12	, , , ]
_ !	173	(oxide with remov\$3) with transfer\$4 with	USPAT	2004/05/05 12	
ĺ	1	chamber	USPAT;	2004/05/05 12	∠:16
		CHURWEL	US-PGPUB		